

Non-dewetting PTFE Membrane



OUR MEMBRANE FOR YOUR SOLUTIONS

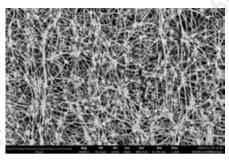
MS-TM-E-4014-EN A/1

Description

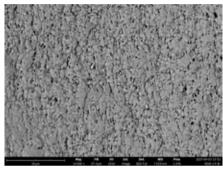
The non dewetting PTFE membrane provided by MS is made by modifying the e-PTFE membrane with a special coating. Through the unique modification technology of MS, hydrophilic functional groups with strong acid, alkali, and oxidation resistance are formed on the surface of PTFE membrane. Therefore, the surface energy of the modified PTFE membrane is improved, and compared to PTFE membrane, it can maintain a hydrophilic state for a long time in aqueous solution after alcohol infiltration. Strong acid filtration is prane Soluti widely used in the semiconductor industry.

Features

- Relatively high membrane surface energy (<30dyn)
- Wide temperature range (-40°C 260°C)
- Thickness (10-50μm)
- Resistant to strong acids, strong bases, and strong oxidants (eg.HNO3, H2SO4)
- Higher resistance to air pressure



Before Modification



After Modification

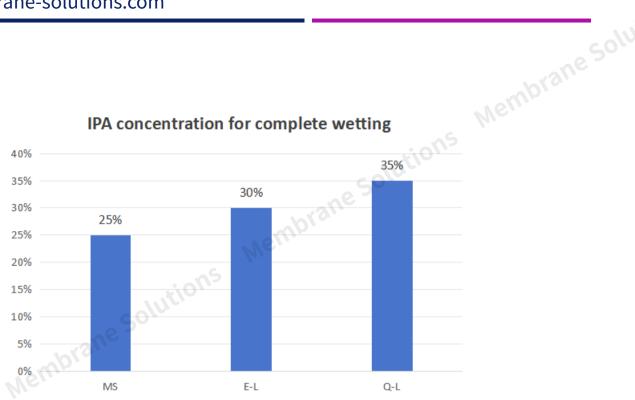
Applications

- Strong acid and strong alkali filtration
- Solvent filtration in the semiconductor industry

Specification

Solvent maradon in the semiconductor industry	Specification Membrane Type Pore Size (μm) Thickness (μm) Water Flow Rate (mL/min/cm²) (mL/min/cm²) 23°C, △p=-10psi Bubble Point (23°C,psi) Particle Retention Efficiency Wettability Non-dewetting PTFE 0.05 10-20 3.2-4.9 21-36(60% IPA) 91.35-96.26% @0.05μm 25%IPA	Applicatio	ns					
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	PTFE @0.05μm				(mL/min/cm ²)		Retention	Wettability
	Mempra		0.05	10-20	3.2-4.9	21-36(60% IPA)		25%IPA
Solutions		500						





rane solutions **Ordering Information**

Series Code	Pore Size	Support Material Code
NDW	005=0.05μm	N=Without Support
		Mempi
	Membrane so	itions



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